



Inverted trinocular LED fluorescence microscope, B, G & UV filter set, IOS

Observation Method - Transmitted Light	Brightfield	Yes
	Phase contrast (Positive type)	Yes
	Darkfield	Yes
Observation Method - Incident Light	Fluorescence	Yes
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Main Body	Туре	Inverted
	Construction material	Aluminum die-cast
Head	Туре	Trinocular (Siedentopf)
	Split ratio	100/0 - 0/100
	Inclination	45°
	Interpupillary distance (mm)	50-75
	Fixing screw for eyepieces	Yes
Eyepieces	Field number (mm)	24
	Magnification	10x
	Planar type	Yes
	Micrometric scale	As optional
	Diameter of micrometer glass (mm)	26
	High eyepoint (for glass wearers)	Yes
	Dioptric adjustement	Yes
	Rubber cup	Yes
	Retractable protections	Yes
Nosepiece	Positions	Quintuple
	Reversed	Yes
	Bi-directional	Yes
	Rotation on ball bearings	Yes
	Objective thread	RMS
	Objective thread	TWO
Objectives	Optical system	×
Objectives	Anti-fungus treatment	Yes
	Parfocal distance (mm) Standard magnifications	45 40x-600x
	Configurable objectives	IOS LWD W-PLAN 4x/0.13, W.D. 10.4 mm
		IOS LWD W-PLAN
		40x/0.60, W.D. 3.1 mm
		IOS LWD W-PLAN

	60x/0.70, W.D. 1.7 mm
	IOS LWD W-PLAN PH
	4x/0.13, W.D. 10.4 mm
	IOS LWD W-PLAN PH
	10x/0.25, W.D. 7.3 mm
	IOS LWD W-PLAN PH
	20x/0.40, W.D. 6.8 mm
	IOS LWD W-PLAN PH
	40x/0.65, W.D. 3 mm
	IOS LWD U-PLAN F
	4x/0.13, W.D. 18.52 mm
	IOS LWD U-PLAN F
	10x/0.30, W.D. 7.11 mm
	IOS LWD U-PLAN F
	20x/0.45, W.D. 5.91 mm
	IOS LWD U-PLAN F
	40x/0.65, W.D. 1.61 mm
	IOS LWD U-PLAN F
	60x/0.75, W.D. 1.04 mm
	IOS LWD U-PLAN F PH
	20x/0.45, W.D. 5.91 mm
	IOS LWD U-PLAN F PH
	40x/0.65, W.D. 1.61 mm

## **OPTIKA MICROSCOPES ITALY**

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Stage Type Fixed + Attachable mechanical stage   Dimensions (mm) 215x250 (fixed stage)   Qaya250 (with mechanical stage mounted)   Moving mechanism Rack and pinion   Moving range (mm) 120x80   Material Anti-scratch painting   Glass round insert Yes   Holder for Petri dish (mm) 38, 54, 65   Holder for Terasaki plate 96 well   Holder for 1 slide Yes   Numerical aperture (N.A.) 0.50   Diaphragms Iris   Slider for phase contrast BF, 4x/10x, 20x/40x positions   Slider for darkfield (dry) Yes   Long working distance Yes   Working distance Yes   Working distance (for LWD) (mm) 28   Extendable working distance (for LWD) (mm) 220   Centrable By rack and pinion	
Focusing System     Type     Abbe       Resonance (for LWD) (mm)     0.50       Diagrams     Brite       Sider for darkfield (dry)     Yes       Contained (dry)     0.50       Position     Sider for Contained (dry)       Processing System     Type       Focusing System     Type       Type     Converse & fine       Fine resolution (mm)     28       Extendable working distance     Yes       Holder for T strast     Strate (dry)       Position     Type       Abbe     Removable       Yes     Numerical aperture (N.A.)       Diaphragms     Iris       Silder for darkfield (dry)     Yes       Long working distance     Yes       Working distance (for LWD) (mm)     28       Extendable working distance (for LWD) (mm)     Yes       Focusable     Strate and pinion	
Moving mechanism     Rack and pinion       Moving range (mm)     120x80       Material     Anti-scratch painting       Glass round insert     Yes       Metal round insert     Yes       Holder for Petri dish (mm)     38, 54, 65       Holder for Terasaki plate     96 well       Holder for 1 slide     Yes       Holder for 2 slides     As optional       Holder for Utermöhl chamber     As optional       Holder for Jutermöhl chamber     Yes       Numerical aperture (N.A.)     0.50       Diaphragms     Iris       Slider for phase contrast     BF, 4x/10x, 20x/40x positions       Slider for darkfield (dry)     Yes       Long working distance (for LWD) (mm)     28       Extendable working distance (for LWD) (mm)     Up to 220       Centrable     Yes       Focusable     By rack and pinion	
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Upper stop to prevent contact Yes	
Adjustable tension Yes	
Transmitted Kohler illumination Full	
Illumination Type X-LED	
X-LED type X-LED8	
Light source power (W) 8	
Brightness control Manual	
Lifetime (hours) > 65,000	
Temperature (K) 6,300	
Max. required power (W) 13	
Dower Supply for Type	
Power Supply for     Type     External       Transmitted     Microscope connector     Jack 21 mm	
Input voltage 100/240 Vac, 50/60 Hz	
Output voltage 12 Vdc 5 A	
ECO function Yes	
LED indicator Yes	
Accessories Included Dust cover Yes	
Allen wrench Yes	
Centering telescope Yes	
Green filter Yes	
LBD filter Yes	
User Manual Digital version (downloadable)	

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Product Dimensions	Height (mm)	545
	Width (mm)	290
	Depth (mm)	720
Product Weight	(kg)	13
Fluorescence	Number of positions	4
Attachment	Blue filter set (included) specs	Excitation: 450 - 490 nm; Dichroic: 495 nm;
		Emission: 500 - 550 nm
	Green filter set (included) specs	Excitation: 540 - 580 nm; Dichroic: 585 nm;
		Emission: 608 - 682 nm
	UV filter set (included) specs	Excitation: 340 - 390 nm; Dichroic: 400 nm;
		Emission: 420LP nm
	Filter dimensions	Excitation: 25 mm diam.;
		Dichroic: 36 mm x 25 mm;
		Emission: 25 mm diam.
	Filter set selection	Manual
	LED source insertion	Motorized
	Field diaphragm	Centerable
Fluorescence Light	Light source	Blue - Green - UV LEDs
Source		Optional LED on request
	Watt (W)	5
		Blue LED: 470 nm
	LED wavelength	Green LED: 560 nm
		UV LED: 385 nm
	Lifetime (hours)	> 65,000
	Brightness control	Yes

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